

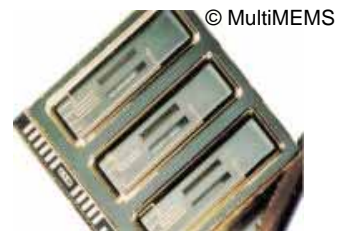
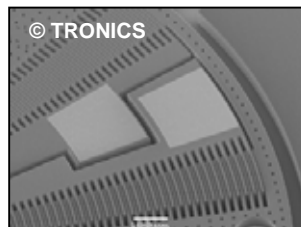
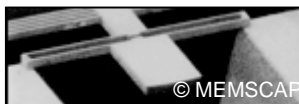


## Standard Multi-Project-Wafer Processes

Coventor's process library provides MEMS designers an overview of existing MEMS processes available in the form of Multi-Project-Wafers (MPW). This allows cost sharing for photolithographic masks and wafer processing. Coventor's foundry library allows the MEMS designer to evaluate and compare processes for user-specific designs. In combination with MPW, Coventor's foundry library provides a direct, secure route to fabrication, at a lower cost.

Coventor's Process Access Kits are available for the following standard processes:

- INTEGRAM – QinetiQ's Metal Nitride Surface Micromachining (MPK) - CMOS compatible
- INTEGRAM - QinetiQ's Deep Etch Silicon-On-Oxide Process (DPK) - CMOS compatible
- INTEGRAM - QinetiQ's 2-Layer Polysilicon (PPK)
- PolyMUMPS – MEMSCAP's 3-Layer Polysilicon Surface Micromachining
- SOIMUMPS - MEMSCAP's Silicon-On-Oxide
- MetalMUMPS - MEMSCAP's Nickel Electroplating
- Tronics - 60um HARM (High Aspect Ratio Micromachining) SOI with wafer capping
- MultiMEMS – SensoNor Infinion Technologies' Bull Silicon-Glass Micromachining for piezoresistive sensors
- IMEPKU - Polysilicon (BETA version)
- HBSRI - Wafer Dissolved Process (BETA version)
- SIMIT- Process for capacitive MEMS (BETA version)
- MicroFabrica 's EFAB - Multiple stack electroplating (BETA version)



Coventor conducts joint training classes with MEMS foundries. For information or related support questions, do not hesitate to contact your local Coventor sales representative or [FoundryProgram@coventor.com](mailto:FoundryProgram@coventor.com)

Other Information:

[Designing Manufacturable MEMS in CMOS Compatible Processes](#)  
[Baolab Microsystems](#)